

L Number	Hits	Search Text	DB	Time stamp
-	11902	(ion adj beam) and etching	USPAT; US-PGPUB; EPO; JPO	2003/07/17 11:43
-	5806	((ion adj beam) and etching) and electrode	USPAT; US-PGPUB; EPO; JPO	2003/07/17 10:08
-	2485	((ion adj beam) and etching) and electrode) and frequency	USPAT; US-PGPUB; EPO; JPO	2003/07/17 10:08
-	146	((ion adj beam) and etching) and electrode) and frequency) and (acoustic adj wave)	USPAT; US-PGPUB; EPO; JPO	2003/07/17 10:09
-	1	((ion adj beam) and etching) and electrode) and frequency) and (acoustic adj wave)) and (piezoelectric adj oscillator)	USPAT; US-PGPUB; EPO; JPO	2003/07/17 10:19
-	4	((ion adj beam) and etching) and electrode) and frequency) and (piezoelectric adj oscillator)	USPAT; US-PGPUB; EPO; JPO	2003/07/17 10:19
-	117	((ion adj beam) and etching) and electrode) and frequency) and (acoustic adj wave)) and piezoelectric	USPAT; US-PGPUB; EPO; JPO	2003/07/17 10:34
-	3	((ion adj beam) and etching) and electrode) and frequency) and (acoustic adj wave)) and piezoelectric) and (moving near4 direction)	USPAT; US-PGPUB; EPO; JPO	2003/07/17 11:41
-	77	((ion adj beam) and etching) and electrode) and frequency) and (acoustic adj wave)) and piezoelectric) and direction	USPAT; US-PGPUB; EPO; JPO	2003/07/17 10:37
-	45	((ion adj beam) and etching) and electrode) and frequency) and (acoustic adj wave)) and piezoelectric) and direction) and (moving or translation)	USPAT; US-PGPUB; EPO; JPO	2003/07/17 11:54
-	118	((ion adj beam) and etching) and electrode) and frequency) and (moving near4 direction)	USPAT; US-PGPUB; EPO; JPO	2003/07/17 11:53
-	7	((ion adj beam) and etching) and electrode) and frequency) and (moving near4 direction)) and translation	USPAT; US-PGPUB; EPO; JPO	2003/07/17 11:42
-	20	((ion adj beam) and etching) and electrode) and frequency) and (moving near4 direction)) and (ion adj beam adj etching)	USPAT; US-PGPUB; EPO; JPO	2003/07/17 11:48
-	695	((ion adj beam) and etching) and electrode) and frequency) and (ion adj beam adj etching)	USPAT; US-PGPUB; EPO; JPO	2003/07/17 11:48
-	1	((ion adj beam) and etching) and electrode) and frequency) and (ion adj beam adj etching)) and (irradiating near4 electrode)	USPAT; US-PGPUB; EPO; JPO	2003/07/17 11:50
-	14	((ion adj beam) and etching) and electrode) and frequency) and (ion adj beam adj etching)) and (irradiating near4 substrate)	USPAT; US-PGPUB; EPO; JPO	2003/07/17 11:50
-	1	((ion adj beam) and etching) and electrode) and frequency) and (ion adj beam adj etching)) and (irradiating near4 substrate)) and (moving near4 direction)	USPAT; US-PGPUB; EPO; JPO	2003/07/17 11:53

-	4	(((((ion adj beam) and etching) and electrode) and frequency) and (ion adj beam adj etching)) and (irradiating near4 substrate)) and (moving or translation)	USPAT; US-PGPUB; EPO; JPO	2003/07/17 11:56
-	185	(((((ion adj beam) and etching) and electrode) and frequency) and (ion adj beam adj etching)) and (moving or translation)	USPAT; US-PGPUB; EPO; JPO	2003/07/17 11:57
-	177	(((((ion adj beam) and etching) and electrode) and frequency) and (ion adj beam adj etching)) and (moving or translation)) and substrate	USPAT; US-PGPUB; EPO; JPO	2003/07/17 11:59
-	177	((((((ion adj beam) and etching) and electrode) and frequency) and (ion adj beam adj etching)) and (moving or translation)) and substrate) and (ion adj beam)	USPAT; US-PGPUB; EPO; JPO	2003/07/17 11:59
-	62	((((((ion adj beam) and etching) and electrode) and frequency) and (ion adj beam adj etching)) and (moving or translation)) and substrate) and (ion adj beam)) and stage	USPAT; US-PGPUB; EPO; JPO	2003/07/17 13:59